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Most Frequently Occurring Classifications of Patents Returned
From A Search of 10799762 on January 26, 2005

Original Classifications

3 430/280.1
2 313/512
2 430/312

Cross-Reference Classifications

4 313/502
4 522/170
4 522/25
3 522/31
2 250/239
2 252/301.36
2 257/100
2 264/137
2 264/495
2 264/496
2 313/501
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2 430/273.1
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2 473/378
2 522/100
2 522/15
2 522/29
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Combined Classifications

5 313/502
5 522/170
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4 522/31
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3 430/270.1
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2 313/501
2 313/503
2 349/153
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2 427/553
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2 428/457
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2 430/273.1
2 430/281.1
2 430/288.1
2 430/319
2 430/325
2 430/327
2 430/945
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2 522/100
2 522/15
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Titles of Most Frequently Occurring Classifications of Patents Returned
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5 313/502 (1 OR, 4 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/483 WITH LUMINESCENT SOLID OR LIQUID MATERIAL
313/498 .Solid-state type
313/502 ..With phosphor embedding material

5 522/170 (1 OR, 4 XR)
Class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A SOLID
POLYMER UTILIZING WAVE ENERGY
522/168 ..Processes of preparing a solid polymer from a
heterocyclic halogen monomer; or compositions therefore
522/170 ...1,2 epoxy

4 522/25 (0 OR, 4 XR)
Class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE
ENERGY
SOLID
522/6 ..Compositions to be polymerized or modified by
wave energy wherein said composition contains at least
one
energy
rate-affecting
oxygen
522/7 ...Contains two or more rate-affecting
materials, at least one of which is specified
522/25Specified rate-affecting material contains
onium group

4 522/31 (1 OR, 3 XR)
Class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A SOLID
POLYMER UTILIZING WAVE ENERGY
522/6 ..Compositions to be polymerized or modified by
wave energy wherein said composition contains at least
one

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specified rate-affecting material; or processes of
preparing or treating a solid polymer utilizing wave

energy

in the presence of at least one specified rate-affecting
material; e.g., nitrogen containing photosensitizer,

oxygen

containing photoinitiator, etc. wave energy in order to
prepare a cellular product

522/31 ...Specified rate-affecting material contains
onium group

3 264/496 (1 OR, 2 XR)

Class 264 : PLASTIC AND NONMETALLIC ARTICLE SHAPING OR
TREATING: PROCESSES
264/484 .Utilizing electrostatic charge, field, force
(e.g., pinning, etc.)
264/494 .Polymerizing, cross-linking, or curing (e.g.,
utilizing ultraviolet radiation, etc.)
264/496 ..while contacting a shaping surface (e.g., in
mold curing, etc.)

3 313/512 (2 OR, 1 XR)

Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/483 WITH LUMINESCENT SOLID OR LIQUID MATERIAL
313/498 .Solid-state type
313/512 ..With envelope or encapsulation

3 385/92 (1 OR, 2 XR)

Class 385 : OPTICAL WAVEGUIDES
385/53 WITH DISENGAGABLE MECHANICAL CONNECTOR
385/88 .Optical fiber to a nonfiber optical device
connector
385/92 ..With housing

3 430/270.1 (1 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/270.1 .Radiation sensitive composition or product or
process of making

3 430/280.1 (3 OR, 0 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/270.1 .Radiation sensitive composition or product or
process of making
430/280.1 ..Radiation sensitive composition comprising
oxirane ring containing component

3 430/312 (2 OR, 1 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/311 .Making electrical device
430/312 ..Including multiple resist image formation

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3 430/315 (1 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR
OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/311 .Making electrical device
430/313 ..With formation of resist image, and etching
of substrate or material deposition
430/315 ...Material deposition only

2 156/273.3 (1 OR, 1 XR)
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/1 METHODS
156/60 .Surface bonding and/or assembly therefor
156/272.2 ..With direct application of electrical,
magnetic, or radiant energy to work
156/273.3 ...Before final assembly; e.g., to cure lamina,
etc.

2 250/239 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/200 PHOTOC CELLS; CIRCUITS AND APPARATUS
250/239 .Housings (in addition to cell casing)

2 250/551 (1 OR, 1 XR)
Class 250 : RADIANT ENERGY
250/200 PHOTOC CELLS; CIRCUITS AND APPARATUS
250/551 .Signal isolator

2 252/301.36 (0 OR, 2 XR)
Class 252 : COMPOSITIONS
252/301.36 INORGANIC LUMINESCENT COMPOSITIONS WITH ORGANIC
NONLUMINESCENT MATERIAL

2 257/100 (0 OR, 2 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/79 INCOHERENT LIGHT EMITTER STRUCTURE
257/100 .Encapsulated

2 257/98 (1 OR, 1 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES
257/79 INCOHERENT LIGHT EMITTER STRUCTURE
257/98 .With reflector, opaque mask, or optical
element (e.g., lens, optical fiber, index of refraction
matching layer, luminescent material layer, filter)
integral with device or device enclosure or package

2 264/137 (0 OR, 2 XR)
Class 264 : PLASTIC AND NONMETALLIC ARTICLE SHAPING OR
TREATING: PROCESSES
264/129 WITH PRINTING OR COATING OF WORKPIECE (OUT OF
MOLD)
264/134 .Coating or impregnating workpiece before
molding or shaping step
264/136 ..Impregnation of batt, sheet, or filament
264/137 ...Heat settable impregnant

2 264/495 (0 OR, 2 XR)
Class 264 : PLASTIC AND NONMETALLIC ARTICLE SHAPING OR
TREATING: PROCESSES

264/484 .Utilizing electrostatic charge, field, force
(e.g., pinning, etc.)

264/494 .Polymerizing, cross-linking, or curing (e.g., utilizing ultraviolet radiation, etc.)

264/495 ..Indefinite length articles

2 313/501 (0 OR, 2 XR)

Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/483 WITH LUMINESCENT SOLID OR LIQUID MATERIAL
313/498 .Solid-state type
313/499 ..Semiconductor depletion layer type
313/501 ...Light conversion

2 313/503 (1 OR, 1 XR)

Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/483 WITH LUMINESCENT SOLID OR LIQUID MATERIAL
313/498 .Solid-state type
313/503 ..With particular phosphor or electrode material

2 349/153 (0 OR, 2 XR)

Class 349 : LIQUID CRYSTAL CELLS, ELEMENTS AND SYSTEMS
349/56 PARTICULAR STRUCTURE
349/84 .Having significant detail of cell structure only
349/153 ..Liquid crystal seal

2 385/88 (1 OR, 1 XR)

Class 385 : OPTICAL WAVEGUIDES
385/53 WITH DISENGAGABLE MECHANICAL CONNECTOR
385/88 .Optical fiber to a nonfiber optical device connector

2 427/553 (0 OR, 2 XR)

Class 427 : COATING PROCESSES
427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC, WAVE, OR PARTICULATE ENERGY
427/532 .Pretreatment of substrate or post-treatment of coated substrate
427/553 ..Low energy electromagnetic radiation (e.g., microwave, radio wave, IR, UV, visible, actinic, laser, etc.)

2 427/66 (0 OR, 2 XR)

Class 427 : COATING PROCESSES
427/58 ELECTRICAL PRODUCT PRODUCED
427/64 .Fluorescent or phosphorescent base coating (e.g., cathode-ray tube, luminescent screen, etc.)
427/66 ..Electroluminescent lamp

2 428/457 (1 OR, 1 XR)

Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
428/411.1 COMPOSITE (NONSTRUCTURAL LAMINATE)
428/457 .Of metal

2 428/690 (1 OR, 1 XR)

Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
428/411.1 COMPOSITE (NONSTRUCTURAL LAMINATE)
428/688 .Of inorganic material
428/689 ..Metal-compound-containing layer
428/690 ...Fluorescent, phosphorescent, or luminescent layer

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2 430/273.1 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR
OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/270.1 .Radiation sensitive composition or product or
process of making
430/271.1 ..Identified backing or protective layer
containing
430/273.1 ...Identified overlayer on radiation-sensitive
layer

2 430/281.1 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/270.1 .Radiation sensitive composition or product or
process of making
430/281.1 ..Radiation sensitive composition comprising
ethylenically unsaturated compound

2 430/288.1 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR
OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/270.1 .Radiation sensitive composition or product or
process of making
430/281.1 ..Radiation sensitive composition comprising
ethylenically unsaturated compound
430/288.1 ...Plural, terminal unsaturation

2 430/319 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/311 .Making electrical device
430/319 ..Named electrical device

2 430/325 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/322 .Forming nonplanar surface
430/325 ..Post image treatment to produce elevated
pattern

2 430/327 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

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430/327 .Processing feature prior to imaging

2 430/945 (0 OR, 2 XR)
class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/945 LASER BEAM

2 473/378 (0 OR, 2 XR)
class 473 : GAMES USING TANGIBLE PROJECTILE
473/131 GOLF
473/351 .Ball
473/378 ..Particular cover (e.g., size, material,
dimple pattern, etc.)

2 522/100 (0 OR, 2 XR)
class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A SOLID
POLYMER UTILIZING WAVE ENERGY
522/100 ..Processes involving an ethylenically
unsaturated material derived from poly 1,2-epoxide as
reactant or a solid polymer; or compositions thereof

2 522/15 (0 OR, 2 XR)
class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE
ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A
SOLID
522/6 .POLYMER UTILIZING WAVE ENERGY
.Compositions to be polymerized or modified by
wave energy wherein said composition contains at least
one
specified rate-affecting material; or processes of
energy
preparing or treating a solid polymer utilizing wave
rate-affecting
in the presence of at least one specified
material; e.g., nitrogen containing photosensitizer,
oxygen
containing photoinitiator, etc. wave energy in order
to
522/7 prepare a cellular product
...Contains two or more rate-affecting
materials, at least one of which is specified
522/12Contains compound containing keto group not
part of a ring and a specified rate-affecting material;
or
522/15 contains a specified rate-affecting material and a
nonspecified photoinitiator or photosensitizer
.....Specified rate-affecting material contains
onium group

2 522/28 (1 OR, 1 XR)
class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART

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OF THE CLASS 520 SERIES

522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE

ENERGY WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING MATERIAL; OR PROCESSES OF PREPARING OR TREATING A

SOLID POLYMER UTILIZING WAVE ENERGY

522/6 ..Compositions to be polymerized or modified by wave energy wherein said composition contains at least one specified rate-affecting material; or processes of preparing or treating a solid polymer utilizing wave in the presence of at least one specified material; e.g., nitrogen containing photosensitizer, containing photoinitiator, etc. wave energy in order to prepare a cellular product

one energy rate-affecting oxygen

522/7 ...Contains two or more rate-affecting materials, at least one of which is specified

522/28Specified rate-affecting material contains phosphorous, arsenic, antimony or nitrogen

2 522/29 (0 OR, 2 XR)

class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES

522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE

ENERGY WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING MATERIAL; OR PROCESSES OF PREPARING OR TREATING A

SOLID POLYMER UTILIZING WAVE ENERGY

522/6 ..Compositions to be polymerized or modified by wave energy wherein said composition contains at least one specified rate-affecting material; or processes of preparing or treating a solid polymer utilizing wave in the presence of at least one specified material; e.g., nitrogen containing photosensitizer, containing photoinitiator, etc. wave energy in order to prepare a cellular product

one energy rate-affecting oxygen

522/7 ...Contains two or more rate-affecting materials, at least one of which is specified

522/29Specified rate-affecting material is a metal-containing organic compound

2 522/99 (0 OR, 2 XR)

class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES

522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING MATERIAL; OR PROCESSES OF PREPARING OR TREATING A SOLID POLYMER UTILIZING WAVE ENERGY

522/99 ..Processes involving a polysiloxane having ethylenic unsaturation as reactant or as solid polymer;
or compositions therefore

2 526/222 (0 OR, 2 XR)
 Class 526 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
 OF THE CLASS 520 SERIES
 526/72 ..POLYMERS FROM ONLY ETHYLENIC MONOMERS OR
 PROCESSES OF POLYMERIZING, POLYMERIZABLE COMPOSITIONS
 CONTAINING ONLY ETHYLENIC MONOMERS AS REACTANTS OR
 PROCESSES OF PREPARING
 526/89 ..Polymerizing in the presence of a specified
 material other than monomer
 526/222 ...Material contains organic sulfur compound

2 528/409 (0 OR, 2 XR)
 Class 528 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
 OF THE CLASS 520 SERIES
 528/403 ..FROM HETEROCYCLIC REACTANT CONTAINING AS RING
 ATOMS OXYGEN, SELENIUM OR TELLURIUM, E.G., EPOXY, ETC.
 528/408 ..Polymerizing in the presence of a specified
 material other than a reactant
 528/409 ...Material contains a metal atom

2 528/90 (0 OR, 2 XR)
 Class 528 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
 OF THE CLASS 520 SERIES
 528/86 ..FROM PHENOL, PHENOL ETHER, OR INORGANIC
 PHENOLATE
 528/87 ..From 1,2-epoxy-containing phenolic reactant
 or with 1,2-epoxy-containing reactant
 528/88 ...Polymerizing in the presence of a specified
 material other than reactant
 528/90Material contains a sulfur atom